



Atty,
Dkt. No.

M#

Client Ref.

308270

P-1812.000-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: DIERICHS

Appl. No. 10/775,326

Filing Date: February 11, 2004

Date: July 2, 2004

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Examiner: Unknown

Group Art Unit: 2042 1756

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Brittany Raymond

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BR	AR 3,573,975	04/1971	DHAKA <i>et al.</i>	117	212	
	BR 3,648,587	03/1972	STEVENS	95	44	
	CR 4,346,164	08/1982	TABARELLI <i>et al.</i>	430	311	
	DR 4,390,273	06/1983	LOEBACH <i>et al.</i>	355	125	
	ER 4,396,705	08/1983	AKEYAMA <i>et al.</i>	430	326	
	FR 4,480,910	11/1984	TAKANASHI <i>et al.</i>	355	30	
	GR 4,509,852	04/1985	Tabarelli <i>et al.</i>	355	30	
	HR 5,040,020	08/1991	RAUSCHENBACH <i>et al.</i>	355	53	
	IR 5,121,256	06/1992	CORLE <i>et al.</i>	359	664	
	JR 5,610,683	03/1997	TAKAHASHI	355	53	
	KR 5,715,039	02/1998	FUKUDA <i>et al.</i>	355	53	
	LR 5,825,043	10/1998	SUWA	250	548	
✓	MR 5,900,354	05/1999	BATCHELDER	430	395	
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BR	OR	WO 99/49504	09/1999	PCT	Fukami <i>et al.</i>	X		X	
	PR	EP 0023231	02/1981	EUROPE	TABARELLI <i>et al.</i>	X			
	QR	EP 0418427	03/1991	EUROPE	MIYAKE	X		X	
	RR	EP 1039511	09/2000	EUROPE	MURAKIMI <i>et al.</i>	X		X	
	SR	DD 224448	07/1985	GERMANY	HESSE <i>et al.</i>		X		
	TR	DD 242880	02/1987	GERMANY	KUCH		X		
	UR	FR 2474708	07/1981	FRANCE	LETELLIER		X		
	VR	JP 62-065326	03/1987	JAPAN	MORIUCHI	X			
	WR	JP 62-121417	06/1987	JAPAN	NAKAZAWA	X			
	XR	JP 63-157419	06/1988	JAPAN	NAKASUJI	X			
✓	YR	JP 04-305915	10/1992	JAPAN	OZEKI <i>et al.</i>	X			
✓	ZR	JP 04-305917	10/1992	JAPAN	OZEKI <i>et al.</i>	X			
BR	AAR	JP 06-124873	05/1994	JAPAN	TAKAHASHI	X		X	

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BR	BBR	M. SWITKES <i>et al.</i> , "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001			
BR	CCR	M. SWITKES <i>et al.</i> , "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356			
BR	DDR	M. SWITKES <i>et al.</i> , "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002			

Examiner *Brittany Raymond*

Date Considered: 2/23/2007

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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BR	AR	6,560,032	05/2003	HATANO	359	656	
	BR	6,600,547	07/2003	WATSON <i>et al.</i>	—	—	
	CR	6,603,130	08/2003	BISSCHOPS <i>et al.</i>	250	492.1	
	DR	6,633,365	10/2003	SUENAGA	355	53	
	ER	2002/0163629	11/2002	SWITKES <i>et al.</i>	355	53	
	FR	2003/0123040	07/2003	ALMOGY	355	69	
	GR	2003/0174408	09/2003	ROSTALSKI <i>et al.</i>	359	642	
	HR	2004/0000627 A1	01/2004	SCHUSTER	—	—	
	IR	2004/0021844 A1	02/2004	SUENAGA	—	—	
↓	JR	2004/0075895 A1	04/2004	LIN	359	380	
BR	KR	2004/0109237 A1	06/2004	EPPEL <i>et al.</i>	—	—	

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		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclosed	No
BR	LR	JP 07-220990	08/1995	JAPAN	FUKUDA <i>et al.</i>	X			
	MR	JP 10-228661	08/1998	JAPAN	KUROKAWA	X			
	NR	JP 10-255319	09/1998	JAPAN	SUENAGA <i>et al.</i>	X			
	OR	JP 10-303114	11/1998	JAPAN	SUWA	X		X	
	PR	JP 10-340846	12/1998	JAPAN	KUDO	X		X	
	QR	JP 2001-091849	04/2001	JAPAN	AIZAKI <i>et al.</i>	X			
	RR	JP 07-132262	05/1995	Japan	HIRAKAWA <i>et al.</i>	X			
	SR	JP 58-202448	11/1983	Japan	KAWAMURA <i>et al.</i>	X			
↓	TR	WO 04/019128	03/2004	PCT	OMURA <i>et al.</i>	X		X	
	UR	WO 03/077037	09/2003	PCT	ROSTALSKI	X		X	
BR	VR	WO 03/077036	09/2003	PCT	SCHUSTER	X			

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	XR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997			
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	ZR	G.W.W. STEVENS, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72			
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BR	BBR	S. OWA <i>et al.</i> , "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)			

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Date Considered: 2/23/2007

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BR						
CR						

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		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclosed	No
BR	DR	DD 206 607	02/1984	GERMANY	WESTPHAL et al.		X		
BR	ER	DD 221 563	04/1985	GERMANY	PFORR et al.		X		
BR	FR	JP 11-176727	07/1999	JAPAN	SHIRAISHI	X			
	GR								

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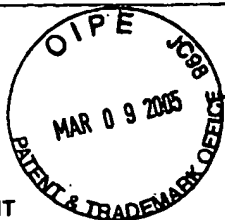
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	MR	G. OWEN et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036							
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	QR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22							
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	SR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521							
✓	TR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004							
BR	UR	B. LIN, "The k_3 coefficient in nonparaxial NA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)							
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Examiner: *Brittany Raymond*

Date Considered: 2/23/2007

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FORM PTO-1449 (modified)
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(PW FORM PAT-1449)
Patent and Trademark Office



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**INFORMATION DISCLOSURE STATEMENT
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Applicant: MARCEL MTM DIERICHs

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	CR 2003/0174408	09/2003	ROSTALSKI et al.	359	642	
	DR 2004/0119954	06/2004	KAWASHIMA et al.	355	30	
<i>BR</i>	ER 2004/0125351	07/2004	KRAUTSCHIK	355	53	
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	GR					

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	IR	JP 2004-193252	07/2004	Japan	Not Available	X			
	JR	WO 2004/053950 A1	06/2004	PCT	OWA	X			
	KR	WO 2004/053951 A1	06/2004	PCT	MAGOME et al.	X			
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	MR	WO 2004/053953 A1	06/2004	PCT	NEI et al.	X			
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	OR	WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.	X			
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	UR	WO 2004/055803 A1	07/2004	PCT	VAN SANTEN	X			
	VR	WO 2004/057589 A1	07/2004	PCT	NEIJZEN et al.	X			
<i>BR</i>	WR	WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.	X		X	
	XR								
	YR								

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